

Chemical vapor deposition and plasma polymerization to produce functionalized silica

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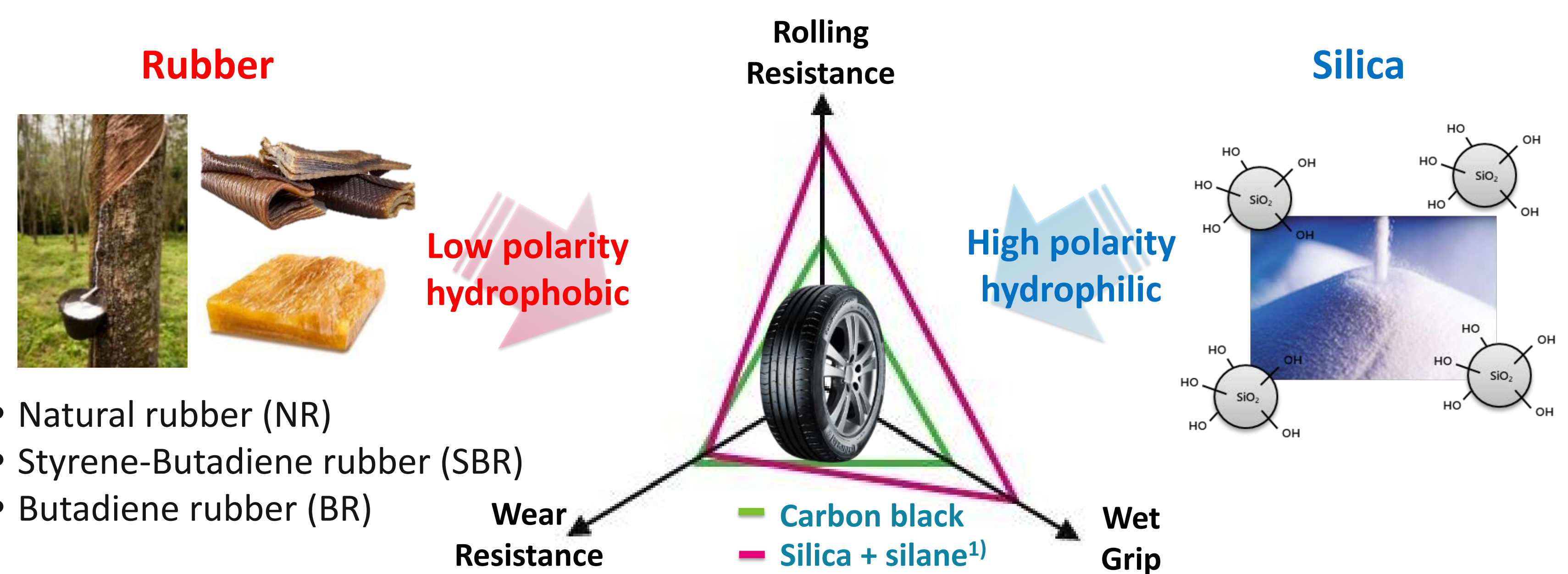
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Introduction

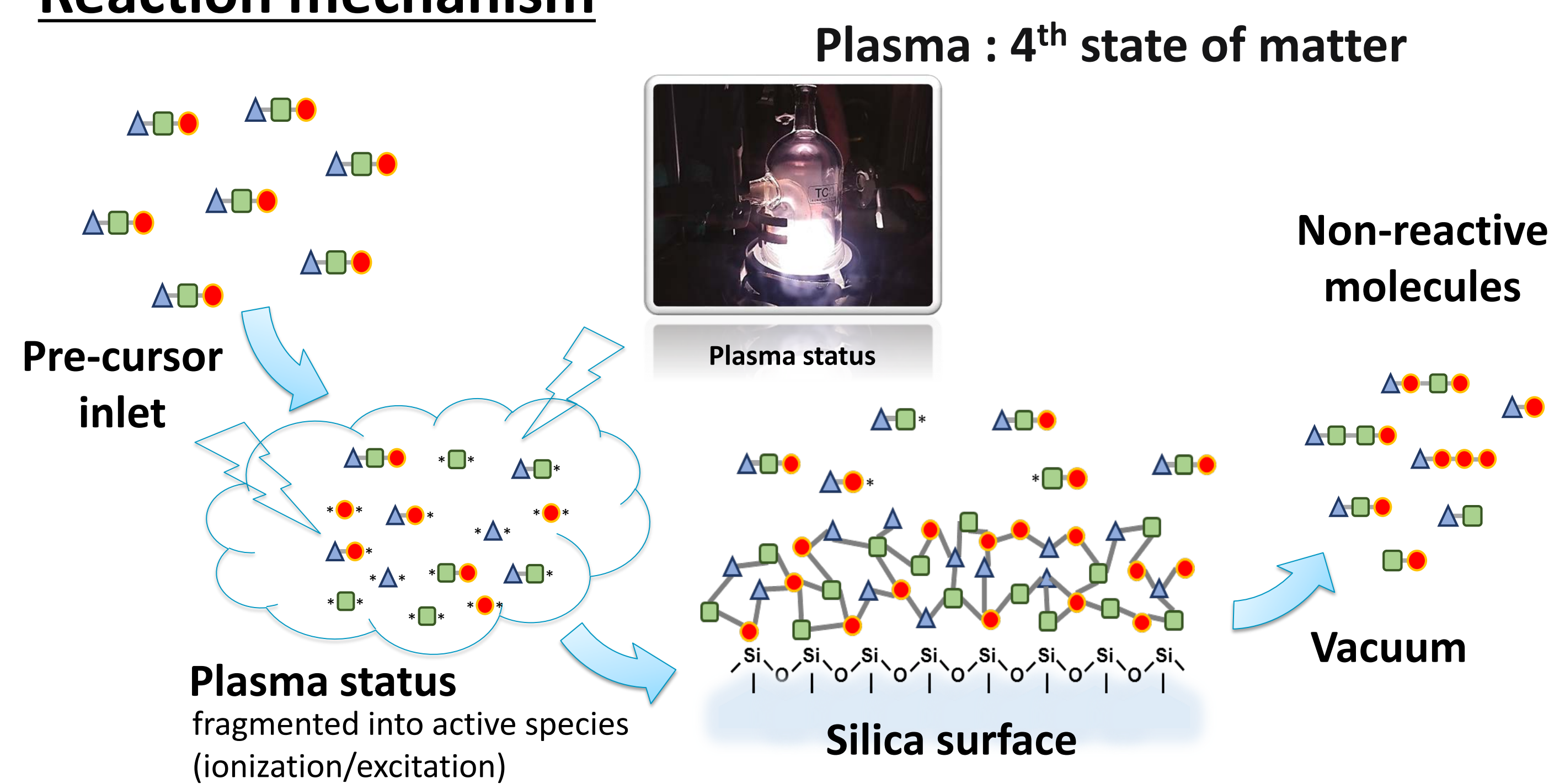
Aim : Novel silica filler system for tire

- Good processibility (easily dispersible)
- Eco-friendly (no hazardous emissions)
- Improving tire performance (Rolling resistance, Wet grip,..)



Plasma Polymerization

Reaction mechanism

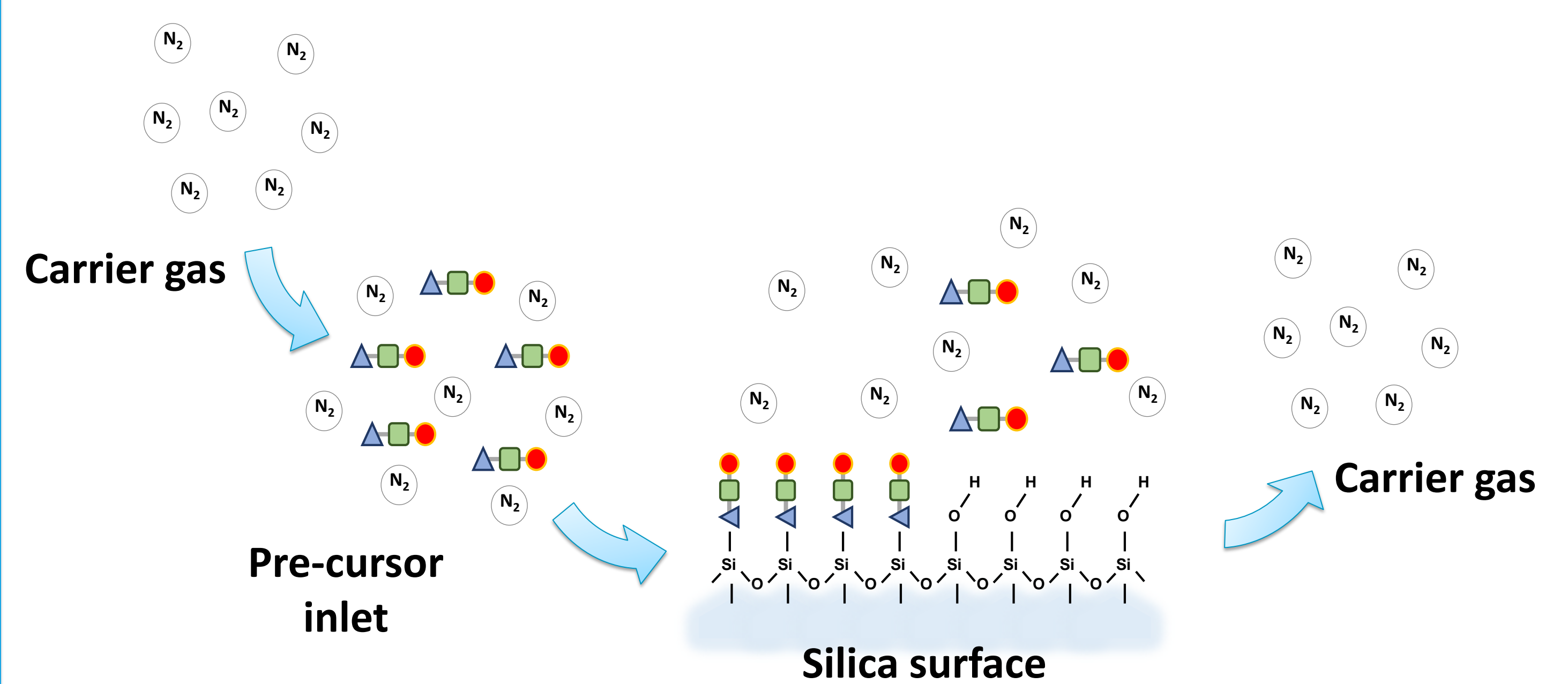


- Strengths**
- Substrate independent process
 - Least alteration of bulk properties of substrate
 - Wide choice of precursors

- Weaknesses**
- Unknown reaction mechanism
 - More difficult upscaling

Chemical Vapor Deposition

Reaction mechanism



- Strengths**
- Adjustable reaction conditions
 - Known reaction mechanism
 - Easier to scale up
- Weaknesses**
- Needs specific precursors having affinity to the substrate
 - Pre-conditioning or multi step reaction (if needed)

Outlook

- Surface energy of treated silica close to polymer matrix for improved compatibility and dispersibility
- Contains moieties after deposition, which can react with the polymer during vulcanization

1) R. Rauline, US Patent 5227425 (1992)